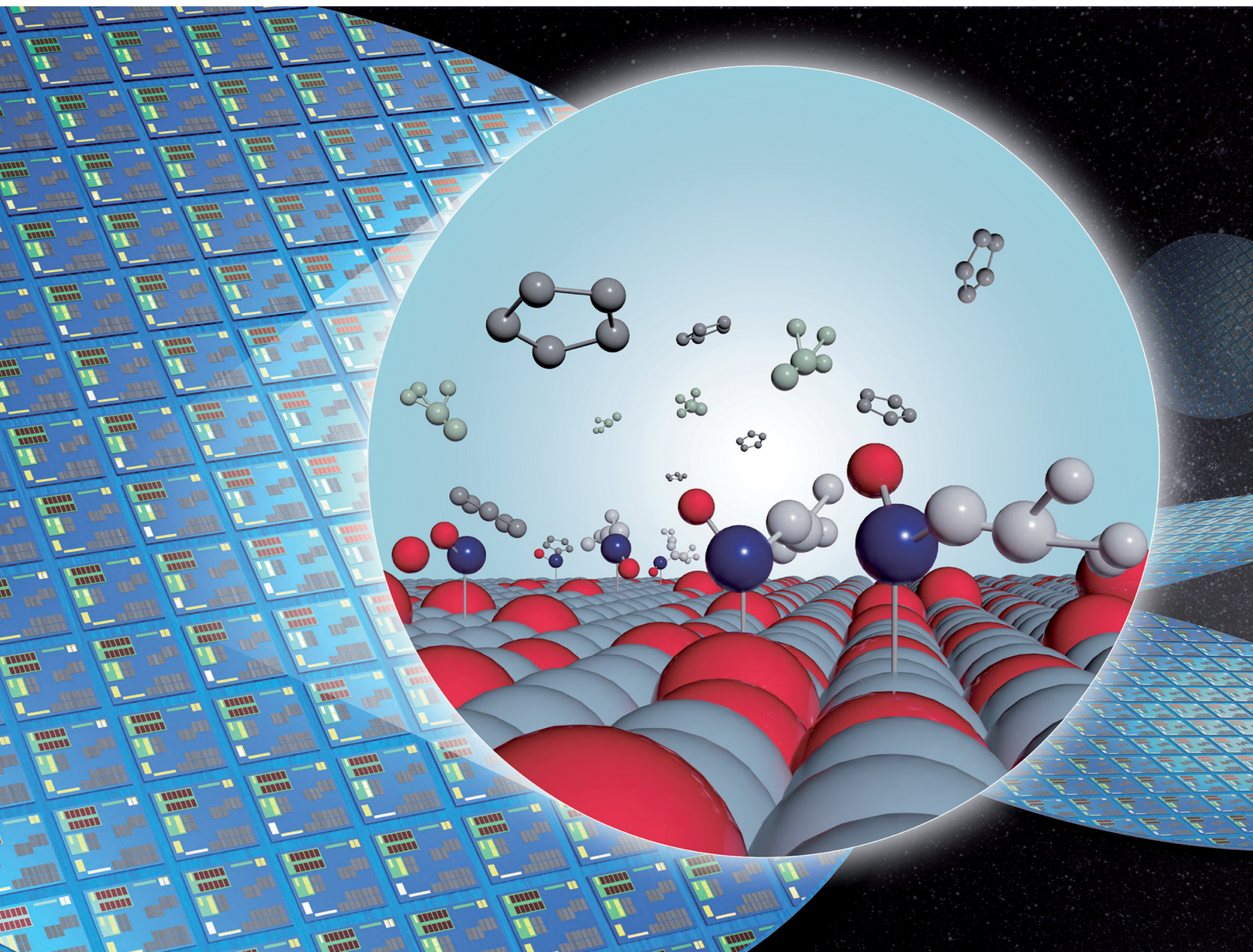


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**COMMUNICATION**

Woongkyu Lee *et al.*  
Suppression of interfacial layers in  $\text{ZrO}_2/\text{TiN}$  capacitors  
by atomic layer deposition using ligand-engineered Zr  
precursors for scalable DRAM